



Radiation Hardening By Design

Low Power, Radiation Tolerant Microelectronics Design Techniques



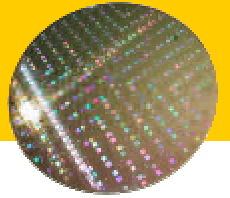
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The foundry problem...



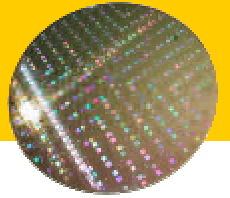
Rad-Hard foundries are leaving the marketplace

- ▼ Reduced demand from military customers
- ▼ Too small volumes
- ▼ Only 1 supplier in Europe left (ATMEL)

Solution: Hardening commercial CMOS technologies

- ▼ US independent
- ▼ more advanced, deep sub-micron technologies possible
- ▼ Higher speed
- ▼ Low power
- ▼ Low volume/mass
- ▼ Low cost
- ▼ => A lot of interest from the (European) space community

Design Against Radiation Effects



Using layout techniques to minimize the radiation impact

- ▼ Free library for European Space Industry

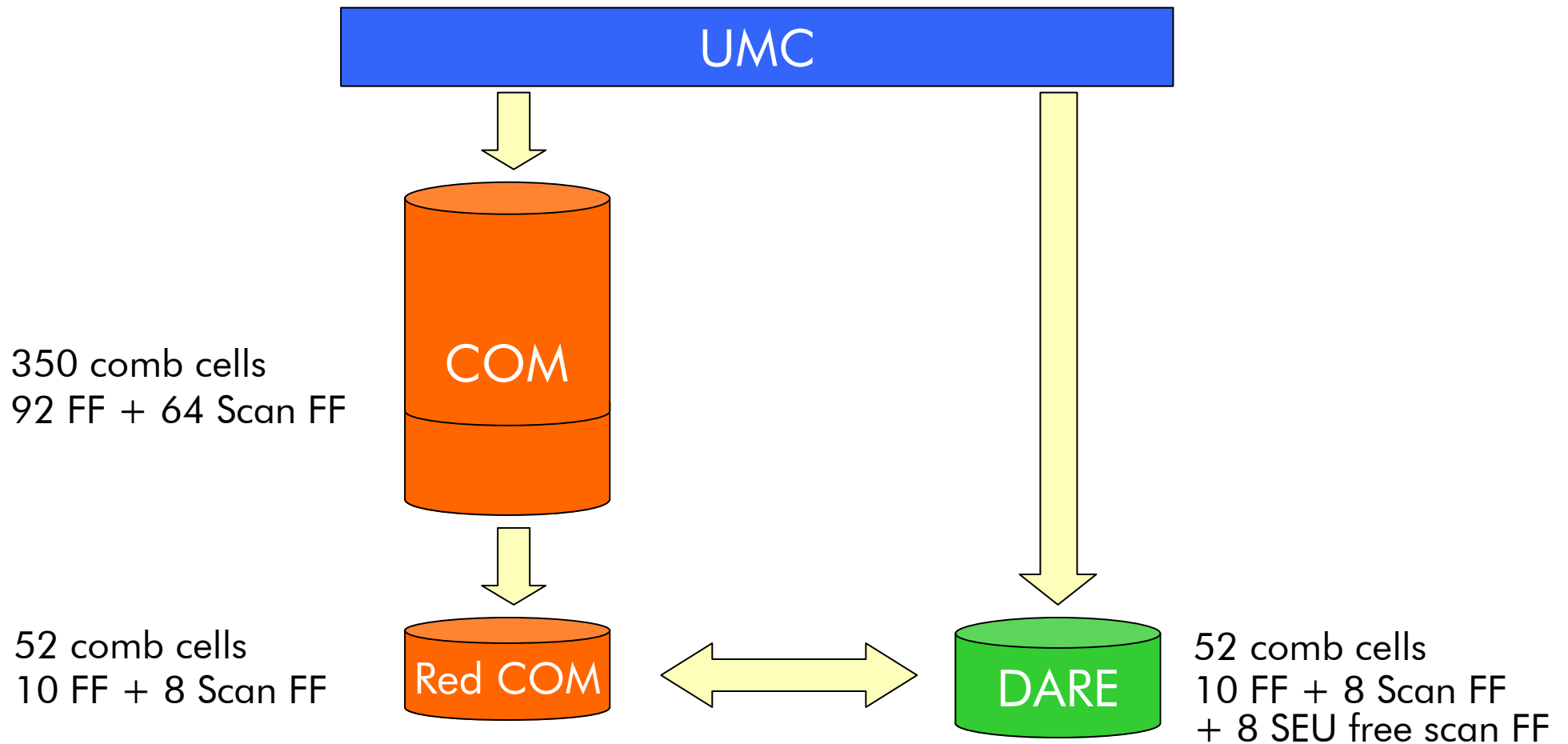
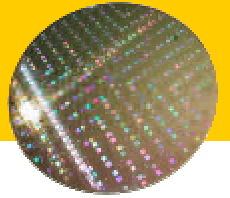
Technology: UMC .18 μm CMOS, 6 metal

- ▼ Available through EURORACTICE (MPW shuttle every month)
- ▼ Very smooth co-operation between IMEC and UMC
- ▼ Stable commercial technology

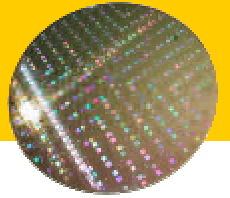
DARE library includes

- ▼ 78 Core Cells
 - Scan equivalents for all flip-flops
 - SEU hardened flip-flops included (HIT cell)
- ▼ 23 In-line IO Pad Cells (+ P/G + Corners + Fillers)
 - 3.3V & 2.5V I/O's
 - Includes LVDS
 - Cold spare & 5V tolerance additions are being investigated
- ▼ Single Port SRAM Compiler
- ▼ PLL

Libraries used



Available EDA tool views



Liberty (.lib) file – for 6 process corners using accurate table lookup timing model

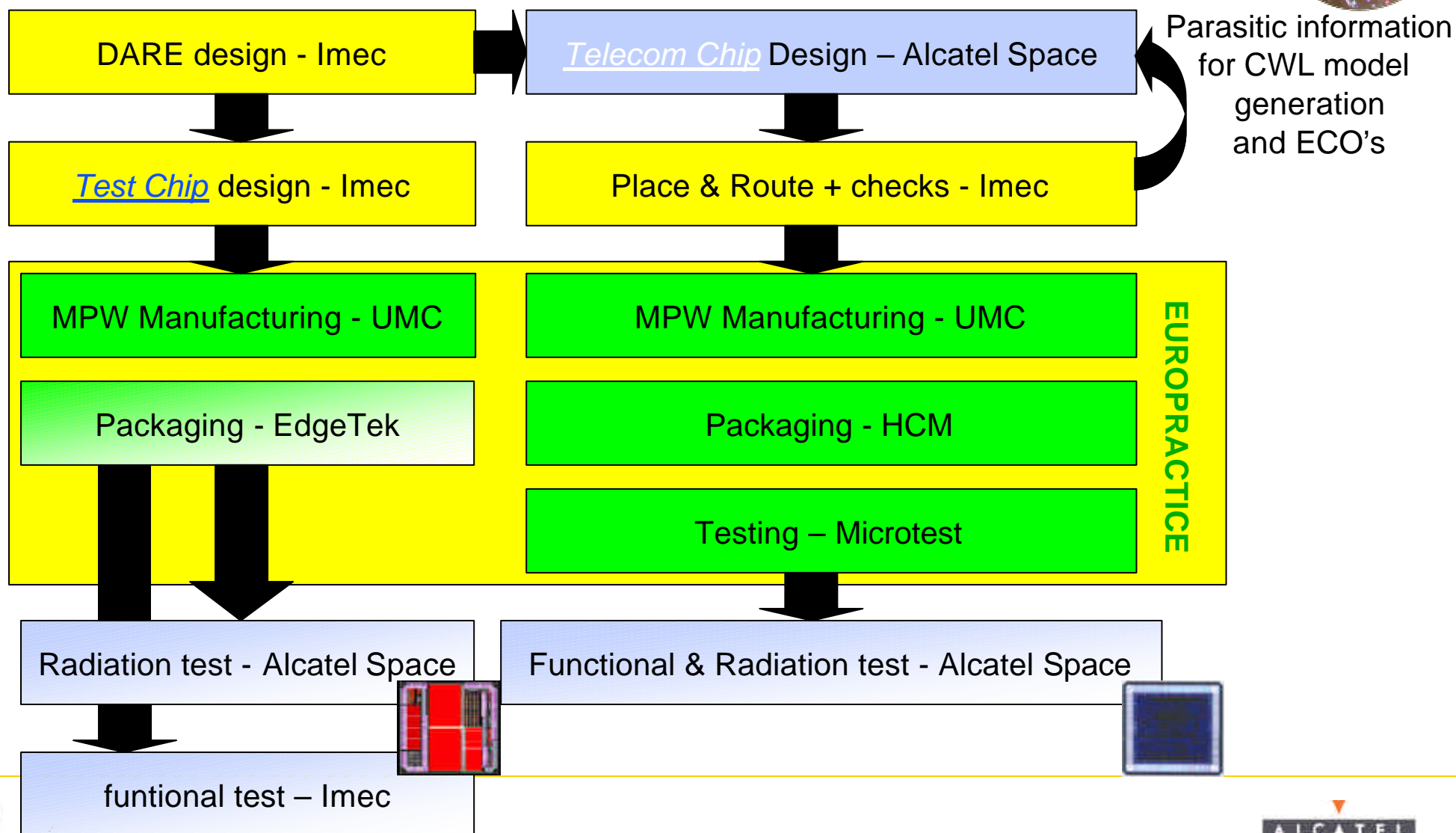
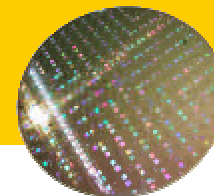
- ▼ Synopsys Design Compiler / PrimeTime
- ▼ Synplicity Synplify ASIC
- ▼ ...

Verilog & VITAL simulation Models

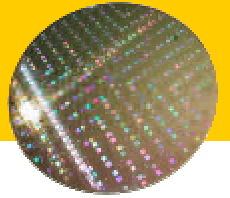
Avant! Apollo layout and timing views

Any LVS tool using CDL input

Project Flow



Actual chip sizes



Commercial Library

- ▼ Pad Limited
- ▼ Chip size : $6.540 \times 6.540 \text{ mm}^2$
- ▼ Core size: $4.039 \times 5.519 \text{ mm}^2$

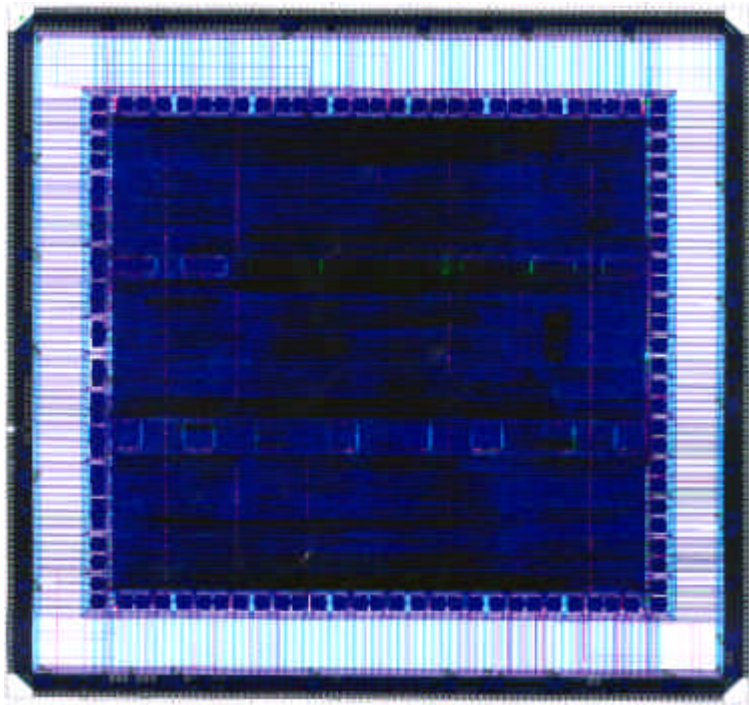
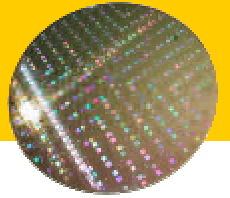
Commercial Library reduced sub-set

- ▼ Same

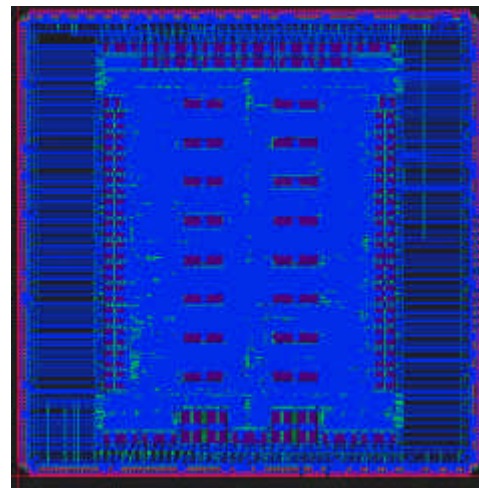
DARE

- ▼ Pad Limited, in-line pads
- ▼ Chip size : $9.418 \times 9.418 \text{ mm}^2$
- ▼ Core size : $7.046 \times 7.344 \text{ mm}^2$
- ▼ \Rightarrow 2 times bigger

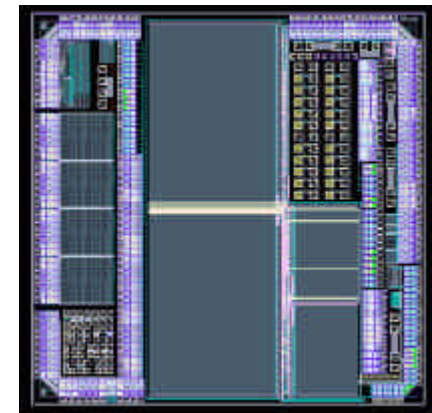
Layouts



DARE DROM

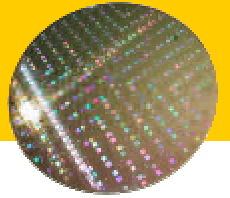


COM DROM
(= Reduced COM)



DIE HARD

What if Staggered IO?



Commercial In-line IO

▼ $6540 \times 6540 = 42.77 \text{mm}^2$

Commercial Staggered IO

▼ $6360 \times 4860 = 30.91 \text{mm}^2$

DARE In-Line IO

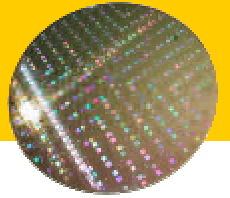
▼ $9418 \times 9418 = 88.7 \text{mm}^2$

DARE Staggered IO (estimated)

▼ $8200 \times 8474 = 69.48 \text{mm}^2$

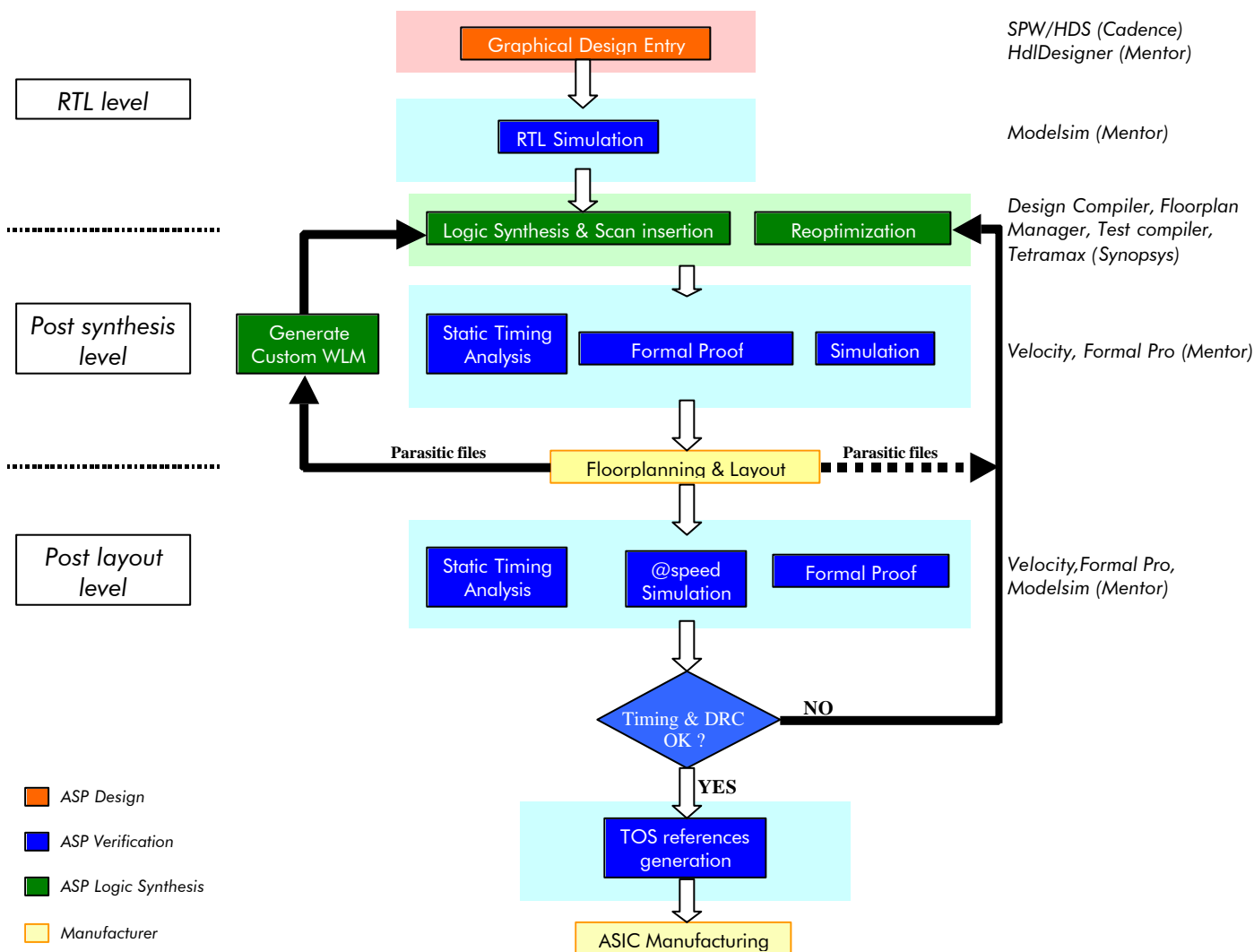
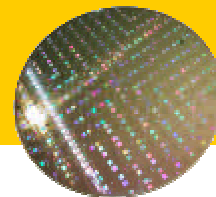
▼ $\Rightarrow 2.25$ times bigger

DROM ASIC

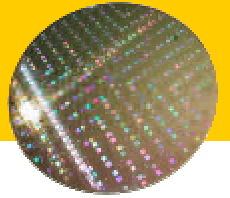


- ▼ DROM : Digital Signal Processing ASIC for Bent Pipe Processor running at 105 MHz
- ▼ 114 SRAMs = 84 kbits
 - 104 SRAMS used at 26.25 MHz max
 - 10 SRAMS used at 52.5 MHz max (~ TPRAM functionality)
- ▼ LVDS I/O
- ▼ Total number of equivalent gates 1.3 MGates
- ▼ Total number of bond pads : 403 pads
- ▼ Package : CPGA 476

DROM design flow



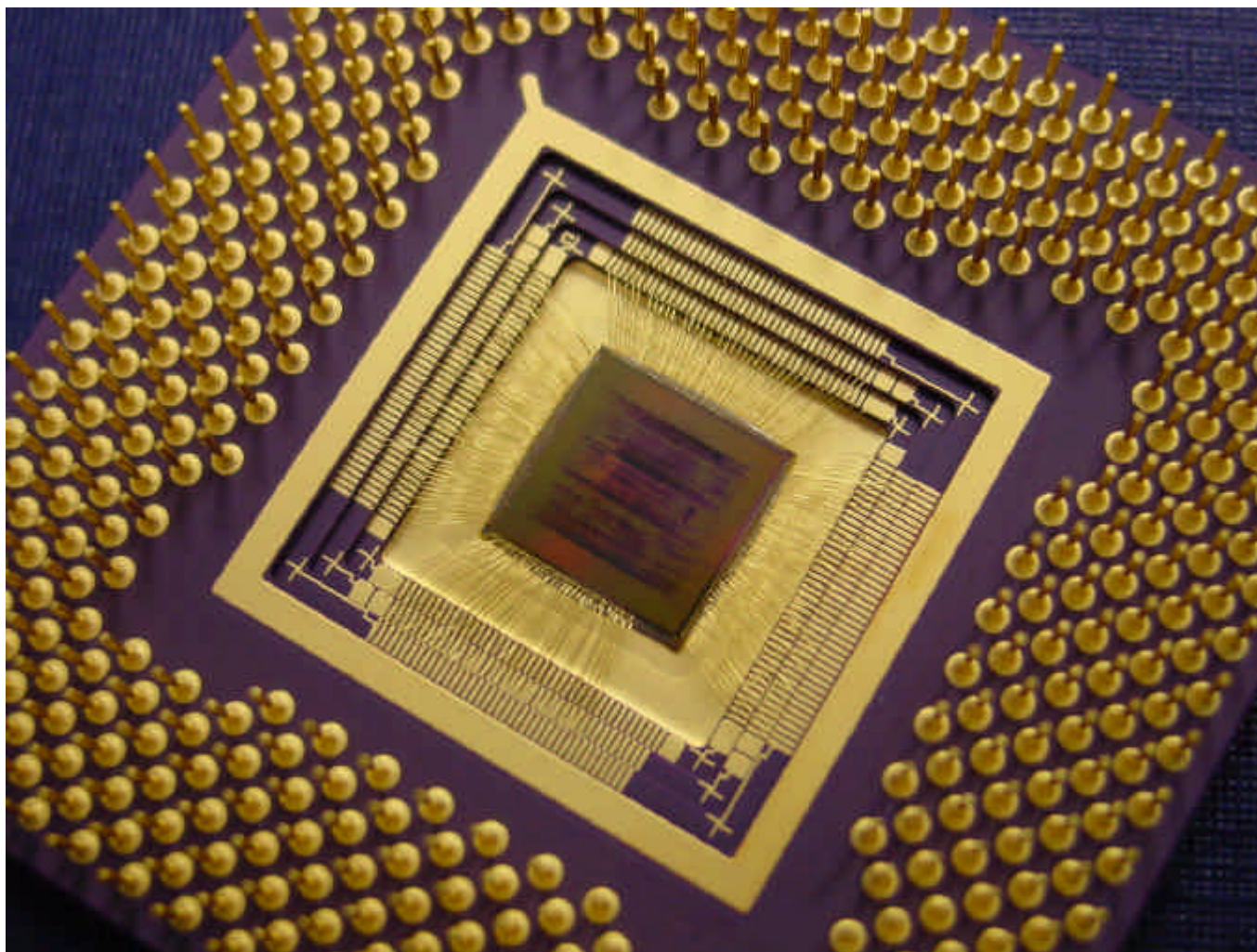
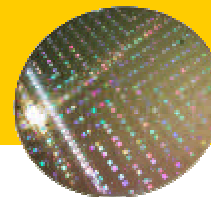
Timing closure after layout



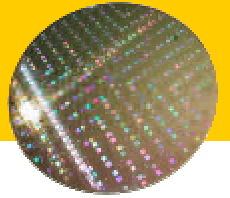
- ▼ Example on a critical path in 105MHz domain
 - ❑ with CWLM : $t_d = 5.24 \text{ ns}$
 - ❑ After 3 layout iterations : $t_d = 6.14 \text{ ns (+17%)}$
 - ❑ important to take some frequency margin during the architecture phase ($\sim 15\%$)

- ▼ Hold violations have to be fixed
 - ❑ at least after first layout
 - ❑ convergence problem after layout of the logic inserted to correct violations

DROM



Library comparison



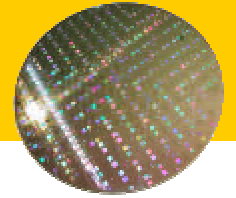
Comparison on operators/ DROM

- area
 - Reduced COM = COM
 - DARE = 3 x Reduced COM
 - DARE/MH1RT : units problem (SOG / Standard cell)
- speed (delay)
 - Reduced COM = COM
 - DARE # Red COM
 - DARE 2 times faster than MH1RT

Power consumption

- COM 0.18 μm : 50 nW/gate/MHz
- DARE 0.18 μm : 180 nW/gate/MHz
- MH1RT 0.35 μm : 400 nW/gate/MHz

Single Event Effect (SEE) Tests



Two types of test have been performed :

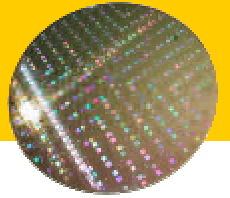
- ▼ **Heavy Ions Test** : The European Heavy Ions Facility of Louvain La Neuve has been used for this evaluation. Ions used in the course of the present evaluation :

Ion Specy	Energy (MeV)	LET (MeV/(mg/cm²))	Range μm
15-N	62	2.97	64
20-Ne	78	5. 85	45
40-Ar	150	14. 1	42
84-Kr	316	34	43
132-Xe	459	55. 9	43

- ▼ **Proton Test** : The CPO (Centre Protonthérapie d'Orsay) Facility of the University of Orsay (France) has been used for this evaluation.

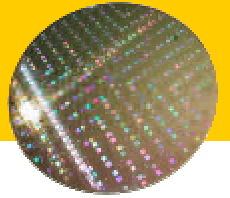
Energy : 150 MeV, 100 MeV, 70 MeV, 50 MeV and 30 MeV.

Single Event Effect (SEE) Tests



- ▼ Selftest Configuration (Autotest) : specific test to easily control the nominal functionality of the ASIC
 - Autotest 1 with a 45.8 MHz carrier waveform
 - Autotest 2 with a temporal ramp
- ▼ Bist Configuration : to evaluate SRAM cells
- ▼ Scan Configuration : to evaluate D flip-flops (implemented physically) placed in several regions on the die
 - SCAN 0 is for « all 0 » initial pattern
 - SCAN 1 for « all 1 » initial pattern.

Main SEE Results

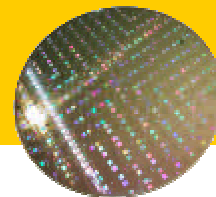


- ▼ No Single Event Latchup (SEL)
- ▼ No Single Event Hard Errors (SHE): Stuck bits
- ▼ No Single Event Functional Interrupt (SEFI)
- ▼ Only Single Event Upset (SEU) observed on basic cells : SRAM, DFF

**=> Impact on DROM functionality is a transient perturbation
but the ASIC recovers after few clock cycles**

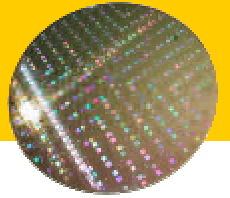
NB : More detailed evaluation of 0.18 μm CMOS basic structures will be performed on the Test Chip March 2004

Main SEE Results



SCAN 1	$t_{(HI \text{ and } p+)} = 12.0 \cdot 10^{-8} \text{ SEU/cell.day (GEO)}$
SCAN 2	$t_{(HI \text{ and } p+)} = 7.7 \cdot 10^{-8} \text{ SEU/cell.day (GEO)}$
BIST	$t_{(HI \text{ and } p+)} = 11.0 \cdot 10^{-8} \text{ SEU/cell.day (GEO)}$
Autotest 1	$t_{(HI \text{ and } p+)} = 5.6 \cdot 10^{-2} \text{ SEU/ASIC.day (GEO)}$
Autotest 2	$t_{(HI \text{ and } p+)} = 7.81 \cdot 10^{-2} \text{ SEU/ASIC.day (GEO)}$

Total Ionizing Dose (TID) Tests



▼ 6 Functional Tests (Same as the ones used for SEE Tests)

- ☐ Selftest Configuration (Autotest) :
 - Autotest 1 with a 45.8 MHz carrier waveform
 - Autotest 2 with a temporal ramp
- ☐ Bist Configuration
- ☐ Scan Configuration : SCAN 0 and SCAN 1

▼ Parametric measurements : I_{cc} (1.8V and 3.3V)

▼ Bias during Irradiation

- ☐ in Autotest Mode

▼ 10 samples + 1 control

▼ Irradiation Steps : 0, 50, 70, 100 krad(Si) Low Dose Rate 200, 500, 700 and 1 Mrad(Si) High Dose Rate

▼ Tests initiated - In progress